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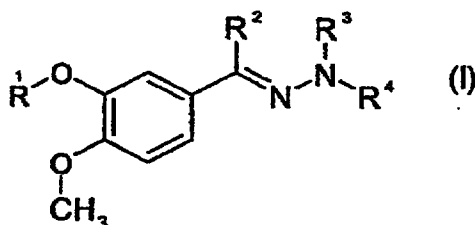
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(54) Title: CATHCOL HYDRAZONE DERIVATIVES, PROCESS FOR PREPARING THE SAME AND PHARMACEUTICAL COMPOSITION CONTAINING THE SAME



(57) Abstract: The present invention provides novel cathcol hydrazone derivatives of formula (I) or pharmaceutically acceptable salts thereof, wherein R¹ is C₁₋₇ alkyl or C₃₋₇ cycloalkyl; R² is hydrogen, hydroxy, C₁₋₅ alkyl or -CH₂CH₂C(=O)NH₂; R³ and R⁴ are independently hydrogen, C₁₋₇ alkyl, -C(=X)-R⁵, or 2-, 3- or 4-pyridyl, pyrimidyl or phenyl substituted with one or two selected from a group consisting of halogen, C₁₋₆ alkoxy, nitro, trifluoromethyl, C₁₋₆ alkyl and carboxyl, or R³ and R⁴ are directly bonded by C₂₋₄ containing oxygen, sulfur or nitrogen to form a heterocyclic ring, X is oxygen, sulfur or NH and R⁵ is C₁₋₇ alkyl, -NHR⁶, CONH₂ or 2-, 3- or 4-pyridyl, pyrimidyl or phenyl substituted with one selected from a group consisting of halogen, C₁₋₆ alkoxy, nitrile, trifluoromethyl, C₁₋₆ alkyl and carboxyl, and R⁶ is hydrogen, hydroxy, NH₂, C₁₋₅ alkoxy, C₁₋₅ alkyl, pyridyl or phenyl.